

	Hits	Search Text	DBs
27	9	\$4lithograph\$5 and ((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near5 layer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	20	((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near5 layer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	24	((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al or chromium or Cr) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near5 layer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB